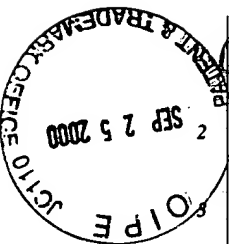


#7/ *Amoldt B*  
*A Ford*  
*10/4/00*



*2/27/00*  
*10/13/00*

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. .... 09/212,726  
Filing Date .... December 15, 1998  
Inventor .... Klaus F. Schuegraf  
Assignee .... Micron Technology, Inc.  
Group Art Unit .... 2813  
Examiner .... E. Kielin  
Attorney's Docket No. .... MI22-1098  
Title: Semiconductor Processing Methods of Chemical Vapor Depositing SiO<sub>2</sub>

RESPONSE TO JUNE 16, 2000 OFFICE ACTION

To: Assistant Commissioner for Patents  
Washington, D.C. 20231

From: Bernard Berman (Tel. 509-624-4276; Fax 509-838-3424)  
Wells, St. John, Roberts, Gregory & Matkin P.S.  
601 W. First Avenue, Suite 1300  
Spokane, WA 99201-3828

Sir:

Responsive to the Office Action dated June 16, 2000, applicant requests reconsideration of the above referenced application in view of the amendments and remarks that follow:

AMENDMENTS

In the Claims

In Claim 43, on line 4 of the claim, insert ~~at~~ at a reduced rate,-- immediately after "precursor."

In Claim 44, on line <sup>3</sup>2 of the claim, delete "silane,."

In Claim 46, on line 2 of the claim, replace "hot" with --wall--.

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